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A Compact Storage Ring for the Production of EUV Radiation

Accelerator Applications 2017



Presentation outline

- Motivation for the study
- Accelerator requirements
 - Optics design
 - Technical sub-systems
 - Undulator
 - DC magnets
 - Vacuum system
 - Injector linac
 - Radio-frequency system
 - Radiation shielding
- Concluding remarks
- Not discussed
 - Non-critical subsystems (diagnostics, controls, power supplies)
 - Injection to storage ring (critical, but work in progress!)



Motivation for this study

- We will describe the design of a compact accelerator with application to the semiconductor industry.
- There is a general consensus within the semiconductor community that EUVL will be the next-generation HVM technique for producing smaller and faster integrated circuits.
- Advances in multi-layer Mo-Si mirrors with high reflectivity (~ 70%) and large bandwidth (~2%) will make 13.5 nm the <u>wavelength of choice</u>.
- The development of metrology methods at EUV wavelengths for mask inspection will be indispensable for the success of EUVL.
 - A mask inspection tool (RESCAN) is currently being developed on an SLS beam-line (Y. Ekinci et. al.)
- However, the development of such an inspection tool only makes sense if a source of EUV radiation, having the required properties, can be built and operated in an industrial environment.
- We propose here a compact (~ 5 m x 12m) synchrotron radiation source for this purpose.



Mask inspection tool





Accelerator requirements

High brightness

 \rightarrow low emittance (nm range)

High stability (10⁻³ range)

ightarrow top-up injection ightarrow full energy booster

High reliability (>99% availability)

 \rightarrow robust design & proven technology

 \rightarrow same requirements as for a 3rd generation light source

+<u>compact layout ($\approx 60 \text{ m}^2$)</u> - in general, this is contradiction with low-emittance.

Innovative solutions

- ightarrow adapt technology of Diffraction Limited Storage Rings
 - \rightarrow multi-bend magnet lattice
 - \rightarrow implementation of undulator
 - ightarrow combined function magnets
 - ightarrow small vacuum chambers with NEG coating
 - + vertical stacking of booster and ring \rightarrow small footprint



Design and optimization

Main criteria for the optimization procedure:

For required performance \rightarrow minimum size and minimum costs

Optimization steps:

- Choice of beam energy and undulator
- Basic storage ring layout and design
- Single particle and collective beam dynamics
- Booster design
- 3-D arrangement of storage ring and pre-accelerators
- Beam transfer and injection process (still WIP)
- Design technical sub-systems



EUV source parameters

Parameter	Unit	Value
Footprint of the storage ring	m²	12x5
Circumference	4	25.8
Beam energy	MeV	430
Beam current	mA	150
Intensity stability	%	0.1
Undulator radiation wavelength	nm	13.5
Flux	ph/s/0.1% BW	1.35x10 ¹⁵
Brilliance	ph/s/mm²/mrad²/0.1% BW	1.8x10 ¹⁸
Coherent fraction	%	6.2



Facility layout

Race-track geometry: Two 5-bend achromat arcs and two straights. One straight for the undulator and one for injection and RF.

- Ring: 430 MeV, 25.8 m
- Booster: $43 \rightarrow 430$ MeV, 24.0 m
- BR transfer line –18.6° inclination
- LB transfer line
- Gun/Linac: 43 MeV, 2.1 m





Lattice features

- Strong horizontal focussing: strong quads → small magnet bore; strong sextupoles to correct chromaticity.
- Weak dispersion (MBA) ensures adequate momentum acceptance despite small aperture
 → needed to reduce particle loss to Touscheck scattering.
- •Skew-quad windings in sextupole to generate some vertical emittance \rightarrow reduce Touscheck scattering.
- •Small β_x at center of undulator \rightarrow minimise source-point size \rightarrow brightness.
- β_v reduced at undulator extremities to reduce particle losses (small vertical gap).
- Magnetic elements would be installed / aligned on girders. Simulations show orbit correction due to misalignments (100 μm, 100 μrad) easily corrected with 1 mrad correction coils.



Nominal storage ring parameters

Circumference [m]	25.8	Energy [MeV]	430
Working Point Q _{x/y}	4.73 / 1.58	Radiation loss/turn [keV]	2.83
Natural chromaticity $\xi_{x/y}$	-9.7 /-6.9	Emittance [nm]	5.50
Momentum compaction α_c	0.0258	Relative energy spread	4.13·10 ⁻⁴
Hor. damping partition J_x	1.54	Damping times τ _{x/y/E} [ms]	16.6 / 25.6 / 17.5

Machine length corresponds to 43 RF wavelengths. 24 "buckets" are filled to leave a gap in the bunch train to combat trapped ions. Total charge in ring is ~ 17 nC (assuming I = 200 mA, to have some margin).

Non-linear beam dynamics studies investigated to evaluate: Dynamic aperture ✓ greater than physical aperture Touscheck scattering → 400 kV RF voltage needed to optimise life-time Intra-beam scattering → some emittance dilution.

Life-times of ~ 15 minutes calculated \rightarrow Top-up frequency > 1 Hz to maintain 0.1% intensity stability.



Trapped Ion effects (M. Ehrlichmann, A Wrulich)

- Positive ions, created by ionisation of the residual gas, can be trapped in the potential well of the electron beam resulting in
 - tune shifts
 - emittance dilution
 - beam instability
- These effects can limit the intensity of the stored beam. This has been studied to check that we can reach the required beam current.
- Mitigation measures must be taken
 - the introduction of "clearing" electrodes to sweep out the ions by electric fields
 - the introduction of a 'gap' in the storage ring bunch train, allowing the ions time to drift to the walls before the arrival of the next bunch. This has been adopted for the EUV source as mentioned earlier.



- Design based on undulator assemblies for SLS and SwissFEL.
 - Field on axis = 0.42 T, λ_u = 16 mm, gap = 7 mm (fixed in operation).
 - Good field region = \pm 12 mm
 - Magnetic material: NdFeB with diffused Dy \rightarrow good combination of $\rm B_r$ and $\rm H_c$
 - \rightarrow less sensitive to demagnetisation due to beam loss (i.e. radiation hard).
- Produces flux / brightness required for mask inspection at 13.5 nm (92 eV).
 - Flux = 1.2x10¹⁵ ph/s/0.1% BW
 - Brilliance = 6x10¹⁷ ph/s/mm²/mrad²/0.1% BW





EUV source brightness curves – 430 MeV comparison with other undulator / dipole magnets





Vacuum system (L. Schulz et. al.)

- Vacuum system must provide sufficiently low base pressure (< 10⁻⁹ mbar) to ensure sufficient beam lifetime due to scattering from residual gas (mainly CO).
 - Elliptical vacuum chamber of 30 mm (H) x 20 mm (V) adopted.
 - "small" chamber to allow strong magnet gradients.
- Low energy ring produces very low heat load ~ 85 W/m (E= 430 MeV, I = 200 mA, $\rho = 1.07$ m) but temperature rise is still significant
 - Forced cooling needed
- Base pressure dominated by photo-desorption due to synchrotron radiation. Simulated using codes Synrad+ (desorption) and Molflow+ (pressure distribution).

\rightarrow full NEG coating of chamber required







Cooling channel 3mm x 6mm



Vacuum performance

 Five vacuum chambers, total length ~ 9 m, form one arc. Stainless steel chamber with 10 sputter ion pumps per arc. Required pressure obtained after ~ 100 Ah of beam time.





- SR lattice optimised to *minimise* number of magnet types: each arc is composed of three 45° dipole combined function bends and two 22.5° dipole CF bends (sector magnets).
- Each arc contains six identical blocks composed of: 2 quads, 1 BPM, 1 combined H/V corrector coil and 1 sextupole (560 mm total length).

Designs for all DC magnets exist. SR magnets are made from solid iron but Booster magnets are made from laminated blocks (to minimise eddy currents during ramp).

Туре	Pieces	L[mm]	B [T]	B' [T/m]	½B"[T/m²]
Gradient bend, solid iron	4 / 6	420 / 840	1.34	-4.10	-17.1
Quadrupole	24	100	0	30	0
Sextupole	16	50	0	±3.0 ^{skew}	580
H/V corrector magnet	12	80	±0.018	0	0

Storage ring magnet parameters



45° SR Dipole





SR quadrupole



H/V corrector coil





Specification of Injector

With 150mA, we have totally only 12.9 nC of charge in the storage ring.

- Charge in Top-Up mode: 13 pC
- Charge to accumulate: 130 pC with 10Hz
- Output energy 20MeV...50MeV
- Normalized emittance < 50μm
- Energy spread < 0.5%
- Pulse to Pulse energy stability < 0.25%

- \rightarrow 1/1000 of charge per shot
- \rightarrow Accumulation in 10s !



The EUV source would use a Photo-Injector linac





- Combine the high brighness travelling wave gun with SwissFEL 2m C-band structure:
 Relaxed gradient, laser profile and repetition rate, Increas number of cells to reach the energy, simplify the couplers and focusing magnet.
- Advantages: Compact and simple design
- Disadvantages: Prototype should be built and tested
- Needs UV-Laser system
- Synchronization more complex ! With $f_b=71.4$ MHz: 5.712GHz = $80f_b$ 499.8MHz = $7f_b$
- Timing for bucket allocation in storage ring more complex (but can still be achieved).



- Power long term stability < 2% rms
- Energy long term stability < 2% rms
- Pulse to pulse < 2% rms

Pulsed laser from industry

- Oscillator synchronizable to external master clock
 Jitter: <250 fs rms
- Gaussian 0.65ps FWHM pulses at 257±5 nm
- with Energy per pulse >0.1 mJ
- Single shot 10Hz 100 Hz repetition rate
- Turn key, industrial class laser system
- Laser system should be located outside the bunker
- Needs evacuated tube to transfer the laser pulse.

C-band travelling-wave gun (R. Zennaro, L. Stingelin)

Output coupler

XY Plot 1 HFSSDesign1 4.50E+007 4.00E+007 3.50E+007 3.00E+007 2.50E+007 \$2.00E+007 1.50E+007 Curve Info 1.00E+007 ComplexMag R E-field at input coupler 1 : LastAdaptive ='19.27455418mm' slot x='15.9 5.00E+006 0.00E+000 20.00 40.00 60 00 80.00

Distance (mm)

Short input coupler

• Based on the SwissFEL 2m C-band structure

- Phase advance: 2π/3
- Group velocity: 3.1% ... 1.3%c
- Iris opening radius:
 7.2 ... 5.4mm
- r/q: 7.2 ... 8.5k**Ω**/m
- Compact coupler (to slide Solenoid on)
- 41 MV/m (cathode) for 33 MW

100 0



Storage ring RF parameters – derived from beam parameters.

Storage ring RF parameters

Revolution Freq.	11.62MHz	Momentum compaction	0.0253
Beam Current	170mA	Energy Spread	0.0004
Energy Loss / Turn	2.8keV	Radiated Power	496W
Long. Damping	16.3ms Main RF Frequency		499.8MHz
Harmonic Number	43 Quality Factor Q ₀		40'000
Shunt Impedance	3.4MΩ	3.4MΩ Over Voltage	
Gap Voltage	400kV	400kV Opt. Voltage in 3HC	
RF Acceptance	2.3%	Quality Factor Q ₀ In 3HC	~13'000
Sync. Phase	0.44 ⁰	Min. Shunt Impedance for passive cavity	84MΩ (3HC)
Cavity Wall Loss	24kW	Shunt Impedance for one active	1.76 ΜΩ
Coupling Factor	1.021	harmonic cavity	
Opt. Detuning for Matching	-18kHz	RF-Power for 1 Active 3HC	~5.2kW
Bunch length	11ps (no HC)	Bunch length	45ps (3HC)
Sync. Frequency	148kHz (no HC)	Landau Damping Rate	~70'000 s ⁻¹



SR Radio-Frequency system (P. Craeivich)

Full list of RF parameters derived from beam parameters (last slide)
Identification of hardware requirements – use existing commercial solutions
RF cavity, power source, waveguide, phase/amplitude regulation
Studies of instability thresholds → shows advantage of 3rd Harmonic Cavity (3HC)
Microwave instability driven by ring impedance; CBI driven by longitudinal or transverse
Higher Order Modes of the RF cavity.







65 kW solid state amp.

ALS 3rd harmonic cavity



Radiation shielding (R.M. Bergmann)

 Performed using codes MCNPX 2.7.0 (local) / MCNP 6.1 (outer wall) Loss rates ~ 1.2x10⁸ electrons/s at 430 MeV → ICRP data used to convert flux to dose rates. Losses dominated by storage ring.



Shielding model: Local (I), outer-wall (r) – material: concrete (g), lead (g), borated polyethelyne (o).



270 tonnes lead and 65 tonnes borated polyethelyne required for adequate shielding.

Not fully optimised!



Does it all fit? 3-D integration





In summary: Conceptual design and systems studied

- Optimization undulator vs. storage ring
- \rightarrow Conceptual design
 - Lattice design
 - − layout & performance ✓
 - − non-linear dynamics ✓
 - beam lifetime ✓
 - ion trapping \checkmark
 - injection & extraction (WIP)
 - Undulator 🗸
 - DC-Magnets ✓
 - Pulsed magnets (WIP)
 - − RF-systems ✓
 - Vacuum system 🗸
 - Radiation shielding ✓



This study has been the work of a number of people:

M. Aiba. R.M. Bergmann, T. Bieri, P. Craievich, M. Ehrlichman, Y. Ekinci, T. Garvey,C. Gough, Ph. Lerch, A. Mueller, M. Negrazus, L. Rivkin, C. Rosenberg, L. Schulz,L. Stingelin, A. Streun, V. Vrankovic, A. Wrulich, A. Zandonella Gallagher, R. Zennaro.

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Advanced Accelerator contributed to 3-D integration drawings Technologies

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Many thanks for your attention.